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PN - JP2001172159 A 20010626  
 PD - 2001-06-26  
 PR - JP19990360161 19991220  
 OPD- 1999-12-20  
 TI - LOW IRRITATIVE ANTIBACTERIAL COSMETIC  
 IN - SERIZAWA TETSUSHI; SATO ENKO; UDAGAWA AKIHIRO; YOKOMAKU ATSUSHI  
 PA - LION CORP  
 IC - A61K7/48

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TI - Low irritation anti-microbial cosmetics for skin, comprises blend of specific anti-microbial agent and predefined labiatae plant solvent extract  
 PR - JP19990360161 19991220  
 PN - JP2001172159 A 20010626 DW200168 A61K7/48 009pp  
 PA - (LIOY) LION CORP  
 IC - A61K7/00 ; A61K7/06 ; A61K7/48  
 AB - JP2001172159 NOVELTY - A cosmetics comprises blend of anti-microbial agent of 1-hydroxy-2-pyridone group compound and its salt, benzalkonium chlorides, benzethonium chlorides, hinokitiol, isopropyl methyl phenol, trichlorocarbanilide and/or zinc pyrithione, and labiatae plant solvent extract of salvia miltiorrhizae, coleus forskohlii, Rosmarinus officinalis and/or lamium album.  
 - DETAILED DESCRIPTION - A cosmetics comprises blend of anti-microbial agent of 1-hydroxy-2-pyridone group compound and its salt, benzalkonium and benzethonium chlorides, trichlorocarbanilide isopropyl methyl phenol, hinokitiol, trichlorocarbanilide and/or zinc pyrithione, and labiatae plant solvent extract of Salvia miltiorrhizae, Coleus forskohlii, Rosmarinus officinalis, Lamium album, Isodon japonicus, Perilla frutescens, Lavandula vera and/or Melissa officinalis.  
 - USE - For skin and hair (claimed).  
 - ADVANTAGE - The low irritation anti-microbial cosmetic has excellent sterilization effect. The cosmetic does not cause skin and mucous membrane irritation, and is safe. The cosmetic is prepared in various dosage forms. The cosmetic inhibits dandruff and itchiness and exertion of hair restoring effect. The cosmetic has excellent effect on acne.  
 - (Dwg.0/0)  
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 TI - LOW IRRITATIVE ANTIBACTERIAL COSMETIC  
 AB - PROBLEM TO BE SOLVED: To provide a low irritative antibacterial cosmetic which has an excellent antibacterial effect and high safety, scarcely irritates the hair and the skin, and can widely be prepared into various dosage forms such as hair cosmetics and skin cosmetics.  
 - SOLUTION: This low irritative antibacterial cosmetic characterized by compounding the solvent extract of one or more Labiatae plants selected from Perilla frutescens, Lavandula vera, Isodon japonicus, Rosmarinus officinalis, Melissa officinalis, Lamium album, Salvia miltiorrhiza, and Coleus forskohlii into an antibacterial cosmetic containing one or more compounds selected from 1-hydroxy-2-pyridone compound and its salt, benzalkonium chloride, benzethonium chloride, isopropylmethylphenol, hinokitiol, trichlorocarbanilide and zinc pyrithione as an antibacterial agent.

I - A61K7/48 ;A61K7/00 ;A61K7/06